O range Peel coupling in granular ferrom agnetic Im s

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W e present magnetoresistance (MR) measurements performed on magnetic tunnel junctions in which one of the electrodes is a granular ferrom agnetic lm. These junctions exhibit a zero eld resistance dip. The dip magnitude depends on the size of the grains. We interpret these results as a consequence of the orange peele ect between the continuous ferrom agnetic lm and the magnetic grains. The coupling is found to be much stronger than that between continuous ferrom agnetic layers.

PACS: 75.70 Ak, 75.47 De, 75.75.+ a

GMR (giant m agnetoresistance) and TMR (tunneling m agnetoresistance) devices are prim ary candidates in future m agneto-electronic applications and m edia [1, 2, 3, 4, 5]. The ability to create arrays of m agnetic junctions on m icro sized areas can enhance storage size drastically and enable the production of non volatile ultra-dense RAM chips. G ranular ferrom agnets have a prom ising potential to act as a further step in this direction since a single junction m ay be able support num erous bits, considerably increasing the possible storage densities.

All applications based on GMR and TMR e ects require high quality multilayers constructed of thin ferromagnetic and non-magnetic Ims. The performance of the devices depend strongly on the morphological and structural properties of the Im s as well as their physical characteristics. Am ong the crucial factors is the interlayer coupling between two ferrom agnetic layers separated by a non-m agnetic spacer. This coupling m ay be a sum of several di erent mechanisms, of which three appear to be dom inant. The rst is pinhole coupling, which results from structural defects in the spacer and m ay destroy MR e ects altogether. The second is the RKKY interaction which oscillates with the spacer thickness. This coupling is due to indirect exchange mechanism and applies only to conductive barriers (GMR multilayers). The third mechanism is the N celC oupling [6], also named O range PeelE ect (OPE), which applies both to conducting and to insulating spacers. This coupling utilizes the surface waviness of correlated layers to produce ferrom agnetic interaction between ferrom agnetic layers that could otherwise be antiferrom agnetically coupled. The mechanism is based on the fact that the waviness of the magnetic Im creates dipoles on the surface. A second layer with correlated waviness placed on top and separated by a non-m agnetic spacer, experiences sim ilar m om ent orientation due to dipole-dipole interaction as illustrated in

gure 1a. Such ferrom agnetic coupling reduces the GMR signalwhich requires antiferrom agnetic orientation at low

elds. Hence, a lot of e ort is invested in an attempt to m inim ize this coupling in order to improve the performance of GMR/TMR elements [7, 8, 9, 10, 11, 12].

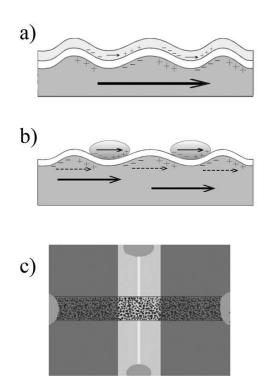
The basic N eelm odel was derived for two in nitely thick magnetic layers separated by a non magnetic spacer [6]. K ools et al [13] extended the theory to included the nite size of the m agnetic layers and obtained the follow - ing expression for the coupling strength:

$$H_{N eel} = \frac{{}^{2}h^{2}M_{P}}{p \overline{2} t_{F}} 1 exp \frac{2 p \overline{2}t_{P}}{p \overline{2}t_{P}} exp \frac{2 p \overline{2}t_{s}}{(1)}$$

where h and are the amplitude and wavelength of the layer waviness. t_F , t_p and t_s are the thicknesses of the free layer, the pinned layer and the spacer respectively, and M $_P$ is the magnetization of the pinned layer.

So far, N eel coupling was studied only between continuous ferrom agnetic layers. O ne m ay ask whether a sim ilar e ect can take place between a ferrom agnetic layer and a set of ferrom agnetic grains. This issue can be of great importance for the design of magnetic devices based on granular structures. A -priori there seems to be no reason why OPE should not apply to granular system s providing the size of the grains correlates with the surface roughness of the layer. A schem atic description of such a possible coupling is depicted in gure 1b. In this paper we describe an experimental e ort to explore the OPE in granular system s. W e present m agnetoresistance m easurem ents of m agnetic tunnel junctions consisting of a uniform Nilayer, an insulating spacer and a granular Ni lm. These structures exhibit a sharp magnetoresistance dip at low magnetic elds which are interpreted as signs for the OPE in the single dom ain grains.

The sam ples were prepared using the follow ing schem e: First, a 250A thick N i layer was e-beam evaporated on a Si/SiO substrate through a 1 mm wide mask. The deposition rate was 0.5 A/s and the base vacuum was 10^{-7} Torr. Next, a 100A layer of SiO was deposited in a 10^{-4} m bar oxygen environment through a 0.25 mm wire-shape window leaving a narrow slit on top of the N i layer. A 30A thick A l_2O_3 (the insulating spacer) was then deposited into the window in a $10^{-4} \text{ m} \text{ bar O}_2$ environment and at a rate of 0.2 A/s. The quality of the barrier was con rm ed by m easuring the I-V curves of sim ilar based N i/A l_2O_3 /Pb superconducting junctions. Finally a discontinuous N i Im was grown on top through a narrow strip shadow mask vertical to the continuous N i layer, thus com pleting a 4 term inal junction geom etry of 0.2



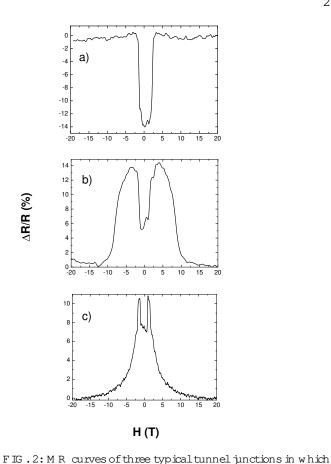


FIG. 1: a) Schematic description of the orange peel e model for two nite continuous layers. Poles created on use surface of the bottom layer (pinned) induce compatible moments in the upper layer (free), thus creating arti cialmagnetic orientation. b) The possible orange peelm odel with a granular layer functioning as the free layer. The grain size is of the order of the waviness. Here the poles induced by the pinned layer create arti cialm agnetic orientations on individualgrains. c) A sketch of the junction geometry.

mm^2 as illustrated in gure 1c.

A major concern with the granular system is the prevention of structural and chemical changes of the Im due to oxidation or annealing. In order to circum vent these problem swe prepared the granular Im susing the technique of quench condensation, i.e. evaporation on a cryocooled substrate within the measurement probe under ultra high vacuum conditions [14, 15, 16, 17]. This technique enables the growth of ultra-clean stable Nigrains with an excellent control over the inter-grain distance and the Im resistance [18, 19]. For our junctions we quench condensed Nidiscontinuous Im on a substrate held at T = 5K and with deposition rate ranging between 0.03-1A s. A s will be shown later the average grain size depends upon this rate. The sam ple resistance and thickness were measured during growth and the process was stopped at a desired resistance of 30-300K . This resistance range insured that the lm had an insulating granular geom etry but, on the other hand, its resistance

the evaporation rate the larger the dip.

the granular Im swere deposited at di erent rates: 1,03 and

0.03 A/s, for a) b) and c) respectively. Notice the di erence

in the magnitude of the zero eld resistance dip. The faster

wasmuch smaller than that of the junction (a few M), thus ensuring that the granular layer can be regarded as an equipotential electrode.

MR studies were performed at T = 4K with external eld applied perpendicular to the junction's plane. All m easurem ents were perform ed using standard lock-in AC techniques and making sure that the I-V curves were in the ohm ic regime. Figure 2 depicts the MR curve of 3 typical junctions in which the granular lm was evaporated at rates of 1,0.3 and 0.03 A/s. It is seen that the sam ples exhibit the following main features: As the eld is reduced from high elds to below 1.2T a resistance rise of 2-15% is observed. This rise is rather gradual and extends up to about 0.4T . Further reducing the eld 0.2T causes a sharp resistance drop so that the below M R curve exhibits a resistance dip around H = 0.W e note that all of our m easured sam ples exhibited these features. However, the magnitudes of the low eld resistance minimum as well as the high eld features depended strongly on the deposition rate of the granular \mbox{lm} .

The high eld resistance increase with decreasing magnetic eld can be expected. The grain anisotropy may be dierent than that of the continuous Im, hence, the grains may switch their magnetic orientation at edds much larger than that of the continuous lm. This leads to a resistance increase. We note that the fact that this feature extends to relatively large edds is unusual for N i where all elements are expected to reach saturation at

elds of H = 0.6T: In a di erent study we suggest [20] that these unusually high elds are a result of the existence of ultra sm all grains that experience unusual high coercivity.

The sharp resistance dip at small elds is more surprising. For this eld range the magnetic elements of the junction are expected to be random ly oriented and the resistance is expected to exhibit a maximum. The sharp m in im um at H = 0 is indicative of m agnetic alignment of the continuous Im with the grains on top. This requires a mechanism for low eld ferrom agnetic coupling between the uniform Ni lm and the granular Nisystem . A natural candidate is the O range Peele ect. As noted above, this e ect was extensively studied for system s containing two ferrom agnetic layers. If a similar mechanism is relevant in a multilayer containing a granular lm, the thickness roughness of the continuous Im has to correlate with the grain average size. Figure 3 shows AFM analysis of a continuous Ni lm and of granular lm s deposited at di erent deposition rates. It is important to note that it is very di cult to obtain exact m orphological information on the quench-condensed granular Im s. A s the system is heated to room temperature the lm s m ay experience som e degree of creep and grains m ay slightly move. However, the AFM pictures can provide a good approximation for the structural features of the system . Figure 3 illustrates that the thickness roughness of our continuous layers has a wavelength of about 400-500 A. For the granular system s, the average grain size grows as a function of deposition rate and approaches the wavelength of the continuous layer roughness for the fastest deposited Im s. A comparison between gures 2 and 3 reveals a clear correlation between the size of the grains and the amplitude of the zero bias dip in qure 2. The larger the grains (and the closer their size to the scale of the roughness in the continuous layer) the larger the dip. G ranular system s which were grown at a rate of 1 A/s have an average size of 400 A and exhibit a dip m agnitude of about 15% (gures 2a and 3a). For a deposition rate of 0.3 A/swe get grain sizes of about 320 A and a dip of 8 % (gures 2b and 3b) and for a rate of 0.03A/s the sizes are 250 A and the dip is 4% (gures 2c and 3c).

This correlation is in agreement with our notion that the resistance dip is due to N eel coupling between the continuous layer and grains on top. We envision that at very high elds both the continuous and the granular

In s are oriented parallel to the eld direction and the resistance is low. As the eld is reduced magnetic moments in the smallest grains start falling into the plain thus increasing the resistance. This process continues down to elds of the order of 0.4T in which the magnetic

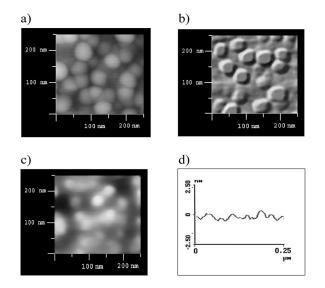


FIG.3: AFM analysis of our layers. a b and c are AFM im ages of granular N i lm s evaporated at rates of 1, 0.3 and 0.03 A/s respectively (corresponding to the samples of gure 2a, 2b and 2c). d is the line scan of a continuous 250 A thick Ni lm.

m om ents of the continuous lm start spraying into the plain. At elds below 0.2T the OPE becomes important and each grain m om ent aligns itself with the m om ent of the dom ain placed below. This leads to the resistance dip at H = 0.

A feature which remains peculiar is the fact that for the high deposition rate samples (gure 2a) the resistance at H = 0 m ay be sm aller than the high eld value. One would expect that at high elds allelem ents are aligned and the resistance should be m in in al. W e note that such anom alies were seen in very dilute granular Im s [21]. In these samples the high eld resistance was often higher than the zero eld state. This e ect was ascribed to magnetic dipole-dipole repulsion that the grains experience when they are aligned perpendicular to the substrate. We propose sim ilar considerations in our junction geom etry. As grains start aligning parallel to each other, all perpendicular to the substrate, dipole-dipole interactions cause m agnetic repulsion between the grain m om entswhich are aligned parallel to each other. This repulsion prevents the dipoles from being fully aligned and therefore the resistance of the junction is not at its minimum at high

elds. At low elds the OPE aligns the grains parallel to the bottom continuous layer and the above reasoning is not relevant, hence a lower tunneling resistance m ay occur. If indeed the cause for the resistance dip is the OPE we can estimate its strength using equation 1. Based on our AFM im ages we use the following geometrical values: h=20A, =400A, $t_F=25A$, $t_P=250A$ and $t_S=25A$. M p for N i is 560 esu/cc to yield a coupling strength of

 $H_{N eel}$ 600 e. This value is similar to coupling strengths estimated and measured in continuous layer structures in which the OPE was studied. Our experimental results, however show that the coupling eld scale extends to magnetic elds of approximately 2000 Oe. This large coupling scale seems to be a unique feature of our granular systems. Figure 2 demonstrates that although the magnitude of the dip depends on the deposition rate of the grains, the eld scale of the e ect is similar for all granular systems. This peculiar feature requires further theoretical treatment.

In conclusion we have measured the magnetoresistance properties of a multilayer containing continuous and granularNi ims separated by an insulating barrier. These exhibit a low eld resistance dip which is indicative of a ferrom agnetic coupling between the lms. The coupling becomes stronger, the larger the correlation between the grain size and the surface roughness of the continuous lm.We interpret these notings as signs for the N eel coupling taking place between the continuous lm and the grains. The coupling seems to be much stronger than that between two continuous layers.

W e gratefully acknowledge illum inating discussions with F.Hellm an and technical help from A.Cohen.This research was supported by the Israel Science foundation grant 326/02.

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